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Libor Juha Saša Bajt Stéphane Guizard Editors

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Contents

v Conference Committee

	DAMAGE MECHANISMS
13533 02	Diagnostics and qualitative analysis of highly charged ions emitted from copper foil exposed to ultrashort x-ray laser pulses [13533-2]
13533 03	Investigating the damage threshold of x-ray mirror (B ₄ C-coated/Si-substrate) at grazing incidence and determining electron collision length at 1keV at the European XFEL (Invited Paper) [13533-3]
	DAMAGE TO OPTICS
13533 04	13.5nm femtosecond laser damage behaviors of EUV multilayer mirrors [13533-4]
13533 05	Formation of carbon deposit on a scintillator screen exposed to x-ray FEL radiation [13533-6]
	TECHNIQUES/INSTRUMENTATION
13533 06	REMINISCE: refurbishment of mirrors to increase sustainability at light sources [13533-12]
	MATERIALS RESPONSE
13533 07	Interaction between EUV and construction materials (Invited Paper) [13533-13]
13533 08	Laboratory and computational studies on radiation damage thresholds in tungsten and boron nitride for first wall applications in IFE reactors [13533-16]

OPTICAL ELEMENTS/MATERIALS

	Of HOAL ELEMENTO/MATERIALS
13533 09	Multilayer Laue lenses for focusing XFEL beams (Invited Paper) [13533-17]
13533 0A	High-transmission CNT-based membrane for EUV [13533-18]
13533 OB	Effects of non-equilibrium in ultrafast irradiation of matter (Invited Paper) [13533-20]
	POSTER SESSION
13533 0C	N₂ buffer gas stopping power for ions in LPP x-ray source [13533-24]